



ATMI-510-CIP
Customer ID No.: 25559

2811

PATENTS & TRADEMARK OFFICE

In re application of: Thomas H. Baum, et al.

Group Art Unit: 2811

U.S. Application No.: 09/954,831

Examiner: TBA

Filed: September 18, 2001

Title: SOURCE REAGENT COMPOSITIONS FOR CVD FORMATION OF GATE
DIELECTRIC THIN FILMS USING AMIDE PRECURSORS AND METHOD OF
USING SAME

#2

CERTIFICATE OF MAILING

Date of Deposit: December 17, 2001

I hereby certify that this Information Disclosure Statement is being deposited with the United States Postal, Postage Prepaid to "Addressee" service under 37 CFR 1.8 on the date indicated above and is addressed Assistant Commissioner for Patents, Washington, DC 20231.

Lee Ann DiLello

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Lee Ann DiLello

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INFORMATION DISCLOSURE STATEMENT

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

Pursuant to 37 C.F.R. §1.56, the attention of the Patent and Trademark Office is hereby directed to the reference(s) listed on the attached PTO-1449. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the reference(s) be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

1. This Information Disclosure Statement is being filed within three months of the U.S. filing date OR before the mailing date of a first Office Action on the merits. No certification or fee is required in accordance with 37 CFR § 1.56 and § 1.97(b).

- 2. This Information Disclosure Statement is being filed more than three months after the U.S. filing date AND after the mailing date of the first Office Action on the merits, but before the mailing date of a Final Rejection or Notice of Allowance.
 - a. I hereby certify that each item of information contained in this Information Disclosure Statement was the first citation of such item by a foreign patent office in a counterpart foreign application, which occurred no more than three months prior to filing the Information Disclosure Statement. 37 C.F.R. §1.97(e)(1).
 - b. I hereby certify that no item of information in this Information Disclosure Statement was cited in a communication from a foreign patent office in a counterpart foreign application or, to my knowledge after making reasonable inquiry, was known to any individual designated in 37 CFR §1.56(c) more than three months prior to the filing of this Information Disclosure Statement. 37 C.F.R. §1.97(e)(2).
 - c. Attached is our check no. ____ in the amount of \$240 in payment of the fee under 37 C.F.R. §1.17(p). Please credit or debit Deposit Account No. 50-0860 as needed to ensure consideration of the disclosed information. Two duplicate copies of this paper are attached.
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- 4. (other):

Applicant does not believe that any additional fee is due in connection with the foregoing.
However, any deficiencies may be charged to the deposit account 50-0860.

Respectfully submitted,

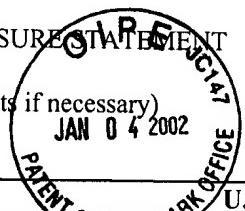


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Date: **December 17, 2001**

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Attorney Ref: 510-CIP

FORM PTO-1449 INFORMATION DISCLOSURE STATEMENT (use several sheets if necessary)		US Dept. of Commerce Patent and Trademark Office		ATTORNEY DOCKET NO. 510 CIP	SERIAL NO. 09/954,831
				APPLICANT Thomas H. Baum, et al.	
				FILING DATE September 18, 2001	GROUP 2811



JAN 04 2002

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		PATENT NUMBER	ISSUE DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	AA	6,159,855	12/12/00	B. Vaartstra			
	AB	6,013,553	1/11/00	R. Wallace, et al.			
	AC	5,820,678	10/13/98	Hubert, et al.			
	AD	5,204,314	4/20/93	Peter S. Kirlin, et al.			
	AE	5,536,323	7/16/96	Peter S. Kirlin, et al.			
	AF	09/414,133		Thomas H. Baum, et al.			10/7/99
	AG	6,015,917	1/18/2000	G. Bhandari, et al.			
	AH	5,972,430	10/26/99	Frank DiMeo, Jr.			
	AI	5,919,522	7/6/99	Thomas H. Baum, et al.			
	AJ	6,110,529	8/28/2000	Robin A. Gardiner, et al.			
	AK	5,820,664	10/13/98	Robin A. Gardiner, et al.			
	AL	5,536,323	7/16/96	Peter S. Kirlin, et al.			
	AM	07/927,134		Peter S. Kirlin, et al.			8/7/92
	AN	5,453,494	9/26/95	Peter S. Kirlin, et al.			
	AO	5,280,012	1/18/94	Peter S. Kirlin, et al.			
	AP	07/615,303		Duncan W. Brown			11/19/90
	AQ	5,225,561	7/6/93	Peter S. Kirlin, et al.			
	AR	07/549,389					7/6/90
	AS	5,876,503	3/2/99	Jeffrey F. Roeder et al.			

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	PUBLICATION DATE	COUNTRY	CLASS	SUBCLAS S	TRANSLATION YES	NO
							X (abstract only)	

OTHER DOCUMENTS (Including Author, Title, Journal-Date, Page Number, Etc.)

Continue on Page 2

EXAMINER	DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.

FORM PTO-1449		US Dept. of Commerce Patent and Trademark Office	ATTORNEY DOCKET NO. 510 CIP	SERIAL NO. 09/954,831
INFORMATION DISCLOSURE STATEMENT (use several sheets if necessary)		APPLICANT Thomas H. Baum, et al.		
		FILING DATE September 18, 2001	GROUP TBA	

O I P E S C I A T
JAN 04 2002
P A T E N T & T R A D E M A R K U S P A C E

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		PATENT NUMBER	TRADEMARK	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	BA	5,976,991	12/2/99	R. Laxman, et al.			
	BB	6,177,135	1/23/01	Frank S. Hintermaier, et al.			
	BC	4,895,709	1/23/90	Richard M. Laine			
	BD	5,139,825	8/18/92	Gordon, et al.			
	BE	5,003,092	3/26/91	Orville T. Beachley, Jr.			
	BF	5,178,911	1/12/93	Roy G. Gordon, et al.			
	BG	6,060,406	5/9/00	Glen B. Alers, et al.			
	BH	5,924,012	7/13/99	Brian A. Vaartstra			
	BI	6,020,243	2/1/00	Robert M Wallace, et al.			

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	PUBLICATION DATE	COUNTRY	CLASS	SUBCLAS S	TRANSLATION YES	NO
							X (abstract only)	

OTHER DOCUMENTS (Including Author, Title, Journal-Date, Page Number, Etc.)

BJ	Jones, et al., "MOCVD of Zirconia Thin Films by Direct Liquid Injection Using a New Class of Zirconium Precursor", Chem. Vap. Dep., Vol. 4, 1998, pp. 46-49.
BK	D.C. Bradley, et al., "Metalorganic Compounds Containing Metal-Nitrogen Bonds: Part I, Some Dialkylamino Derivatives of Titanium and Zirconium", J. Chem. Soc., 1960, 3857).
BL	D.C. Bradley, et al., "Metalorganic Compounds Containing Metal-Nitrogen Bonds: Part III. Dialkylamino Compounds of Tantalum", Canadian J. Chem., 40, 1355 (1962)
BM	S. Giles, et al., "Deposition of (Ti,Al)N thin films by organometallic chemical vapor deposition: thermodynamic predictions and experimental results", Elsevier Science, SA, Surface and Coatings Technology, 94-95 (1997), pgs. 285-290.
BN	Kozoh Sugiyama, et al., "Low Temperature Deposition of Metal Nitrides by Thermal Decomposition of Organometallic Compounds", Journal of the Electrochemical Society, Vol. 122, No. 11, Nov. 1975
BO	R. Juza, et al., "Ammonothermal Synthesis of Magnesium and Beryllium Amides", Angew. Chem. Inte. Ed., 5, (2), 247 (1966).

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